



### Field emission measurement on flat Mo-substrates

Roman Barday

ERL 2013 09.09.2013.

### **BERL**in**Pro=high current Berlin Energy Recovery Linac test facility**



Beam energy	50 MeV
Average current	100 mA
Bunch charge	77 pC
Normalized emittance	1 mm·mrad
Resonance frequency	1.3 GHz

demonstration of the feasibility to use ERL technology for future 4<sup>th</sup> generation multiuser light sources Development of an electron source with I=100 mA and ε<1.0 mm·mrad High average current I<sub>ave</sub>=100 mA
Photomaterials with high QE in the green part of the light spectrum→ cathode work function φ<2.5 eV</li>
Semiconductor CsK<sub>2</sub>Sb is a baseline photocathode for BERLinPro φ(CsK<sub>2</sub>Sb)~1.9 eV; φ(Cs<sub>2</sub>Te)~3.6 eV, φ(Mo)~4.6 eV



Low beam emittance required for BERLinPro demands high field gradient on the cathode surface during beam extraction  $E_{launch}=E_{cath}\cdot sin(\Phi) \Rightarrow$  high peak field  $E_{cath}$  on the cathode surface Field emission grows exponentially with the field amplitude

### **Electron source for BERLinPro**



E<sub>axis</sub>~30 MV/m (E<sub>iris</sub>=45 MV/m) E<sub>kin</sub>=2.3 MeV, I=100 mA→P=230 kW Power limit of ~230 kW by two KEK-style fundamental power couples

Retracted cathode  $z_{cath}$ =-2.5 mm (relative to the backwall)  $\rightarrow E_{cath} \sim 0.57 \cdot E_{axis}$  $E_{cath}$ =17-30 MV/m



## **Limiting factors**:

Field emission (unwanted beam) extracted from the cavity can limit the operation of the SRF gun:

- particles loss in the booster
- damage of the machine components...
- pressure rise (ESD)
- electron-backbombardment (influence on cathode QE, production of secondary electrons, heating,...)

Field emission is relevant for understanding of multipacting, which can also limit the performance of the SRF gun

### **Sources of Field Emission**





Photocathode

0

edge Mo

lat Mo

o/cathode

cathode

Substrate

### Sources of FE:

- Substrate (incl. edges)
- Boundary substrate/cathode
- Cathode

### Field Emission Scanning Microscope in Wuppertal





Regulated voltage scan V(x,y)
Local measurements of emitters I(U)→β<sub>FN</sub>, S<sub>FN</sub>



#### E=k\*V/d

*k* - geometric correction factor (gap, anode diameter, shape,...) *V* - voltage, *d*- gap Truncated conical tungsten anode with a flat tip of diameter ~150 µm (300 µm), gap *d*=50 µm, for a flat surface  $\rightarrow$  E=V/d

Field gradient was adjusted using a 10 kV power supply

### **Polycrystalline Mo-Substrate**



No <u>Dry Ice Cleaning (high pressure jet of pure CO<sub>2</sub>), ionized nitrogen,...</u> FE measurement was performed over the <u>entire</u> surface of the Mo sample Applied voltage was adjust for I=1 nA emission current, gap is constant d=50  $\mu$ m First emission at E=80 MV/m 5 emitters were observed at E=100 MV/m



### **Characterization of the emitters**

#### I(E), enhancement factor $\beta$ , effective emitting area S



# Gap estimation using a long-distance optical microscope

- Centering the anode at the emission site
- Reducing the gap while adjusting HV to maintain a constant current (1 nA)
- Extrapolation to V=0 is set as a gap d=0

### Local Measurements (Emitter 1)







#### Unstable

Non Fowler-Nordheim (F-N) behaviour No emission between 92 MV/m and 101 MV/m Emitter activation (except E<90 MV/m)

<i>S</i> , m <sup>2</sup>	3.4E7	4.3E-2	4.3E-8	1.7E-16	9.6E-18	2.5E-19
β	10.4	14.9	17.6	37.1	46.9	66.2
Pos.	Up1	Up2	Up3	Up4	Up5	Up6
<i>S</i> , m <sup>2</sup>	2.8E-16	9.8E-15	1.6E-16	3.5E-11		
β	44.7	33.9	52.3	24.4		
Pos.	Down7	Down8	Down9	Down10		

### Local Measurements (Emitter 4)







E<sub>onsett</sub>(1nA)=70 MV/m FN-dependence Strong activation E<sub>onsett</sub>(1nA)=46 MV/m

<i>S</i> , m <sup>2</sup>	1.1E-16	5.1E-17	7E-12		
β	64.3	69.4	34.6		
Pos.	Up1	Up2	Up3		
<i>S</i> , m <sup>2</sup>	5.5E-17	6.4E-17	1.3E-15	3.1E-16	1.7E-14
β	92.2	107.2	78.9	94.9	73.1
Pos.	Down4	Down5	Down6	Down7	Down8

### Morphology and Composition of Emitters (Emitter 1)





The emitters were investigated by:

- SEM (Scanning Electron Microscope)
- EDX (Energy Dispersive X-ray)





### Single Crystal Mo-Substrate

5.009 nm

-5.014 nm



No Relay

20X

20X

520 nm White

at centre position

Area: 235.2 x 235.2 um

Op:

 $\frac{Centre}{(235x235) mm^2} S_q=1.7 nm S_a=1.2 nm$ 

at Omm

#### Op: at edge Area: 235.2 x 235.2 um

Points: 230400

QUARTIC

QUARTIC



# Surface of the single crystal Mo sample measured with a white light interferometer



Ionized nitrogen, DIC (5 minutes) Much less particles on the surface First emission was observed at 160 MV/m Strong emission from the edges





### **Heat Treatment**

Cathode preparation  $\rightarrow$  clean surface (heat treatment)

**Temperature dependence:** 

- activation of new emitters
- modification of existing emitters

Heating at 100 °C, 200 °C, 300 °C, 400 °C and 600 °C The most dominant effect was observed after heat treatment at T=400 °C Molybdenum trioxide  $MoO_3$ ?  $MoO_3 \rightarrow 2MoO_2 + O_2$ 



First emission was observed at 80 MV/m for polycrystalline Mo and 160 MV/m for single crystal Mo

Strong emission from the edges of the sample2

It seems that heat treatment of the substrate surface increases the number of emission sites for the same gradient It seems that the emitters become more stable

The most dominant effect was observed after heat treatment at T=400 °C



A. Burrill, A. Jankowiak, T. Kamps, C. Klimm, J. Knobloch, F. Siewert, Helmholtz-Zentrum Berlin

S. Lagotzky, G. Müller, FB C Physics Department, University of Wuppertal